

OK to  
Enter  
RK  
11/6/07

**REPLY UNDER 37 CFR §1.116**  
**EXPEDITED PROCEDURE**  
**TECHNOLOGY CENTER 1700**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of:  
Huan-Just Lin, et al.

Serial No.: 10/688,045

Filed: October 17, 2003

For: FULLY DRY, Si RECESS FREE  
PROCESS FOR REMOVING  
HIGH K DIELECTRIC LAYER

§  
§  
§  
§  
§  
§  
§  
§  
§

Attorney Docket No.  
2003-0065 / 24061.508

Customer No. 42717

Group Art Unit: 1722

Examiner: Robert M. Kunemund

Confirmation No.: 9213

**Mail Stop AF**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

I hereby certify that this correspondence (including any listed enclosures) is being electronically filed in the United States Patent and Trademark Office via the EFS-Web system on October 30, 2007.

  
Linda Ingram

Sir:

**RESPONSE UNDER 37 CFR §1.116**

This Response is submitted in reply to the Office Action mailed on October 4, 2007.  
(Please see the pages that follow).